



Docket No. 740107-135

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of: )

Nobuo SHIMAZU et al. )

Serial No. 09/732,927 )

Filed: December 11, 2000 )

For: MANUFACTURING METHOD OF )  
MASK FOR ELECTRON BEAM )  
PROXIMITY EXPOSURE AND MASK )

Group Art Unit: 2881

Examiner: K. Fernandez

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as First Class Mail in an envelope addressed to: Commissioner for Patents, Washington, D.C. 20231, on November 25, 2002.

K.M. McManus  
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SUBMISSION OF SUBSTITUTE DRAWINGS

Commissioner for Patents  
Washington, D.C. 20231

Sir:

Enclosed please find One (1) sheet (Fig. 1) of formal drawings for review by the Patent and Trademark Office in connection with the above-identified application. Should the enclosed drawing require changes, it is respectfully requested that the Patent and Trademark Office notify the undersigned attorney of same.

Respectfully submitted,

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